## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: Koji NOZAKI et al.

Group Art Unit: 1752

Application Number: 10/623,679

Examiner: Amanda C. Walke

Filed: July 22, 2003

Confirmation Number: 5083

For:

RESIST PATTERN THICKENING MATERIAL, RESIST PATTERN

AND PROCESS FOR FORMING THE SAME, AND SEMICONDUCTOR DEVICE AND PROCESS FOR

MANUFACTURING THE SAME

Attorney Docket Number:

030891

Customer Number:

38834

## SUBMISSION UNDER 37 C.F.R. §1.114

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

November 13, 2006

Sir:

This Submission is being filed concurrently with a Request for Continued Examination pursuant to 37 C.F.R. §1.114.

Amendments to the Claims begin on page 2 of this paper.

Remarks begin on page 11 of this paper.

11/15/2006 MAHMED1 00000068 10623679

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